

Global PVD Evaporation Source Supply, Demand and Key Producers, 2026-2032

<https://marketpublishers.com/r/G0A405E009A3EN.html>

Date: January 2026

Pages: 132

Price: US\$ 4,480.00 (Single User License)

ID: G0A405E009A3EN

Abstracts

The global PVD Evaporation Source market size is expected to reach \$ 604 million by 2032, rising at a market growth of 5.2% CAGR during the forecast period (2026-2032).

In 2025, global PVD Evaporation Source production reached approximately 13.73 million units with an average global market price of around US\$30 per unit. Single-line annual production capacity averages 460 k units with a gross margin of approximately 26%. The upstream of the PVD Evaporation Source industry primarily includes high-purity metals, non-metallic targets, and evaporation source equipment, focusing on the semiconductor, optical, and electronic fields. In terms of downstream applications, the vacuum evaporation process accounts for the highest proportion, reaching 60%, with film deposition accounting for 30%, and other applications making up 10%. The technological iteration and capacity expansion in advanced semiconductor processes (such as high-k metal gates, ALD seed layers), new display technologies (such as Micro-LED, flexible OLED), and precision optical devices are driving the evolution of evaporation sources towards higher purity, more stable long-term evaporation rates, better film uniformity, and directional deposition capabilities for complex substrates. The core business opportunities lie in the development of high-temperature compatible evaporation sources for compound semiconductors (such as GaN, GaAs), linear evaporation source arrays for efficient large-area flat panel display production, and intelligent evaporation systems equipped with real-time film thickness and rate sensors to achieve closed-loop control, thereby addressing key technical bottlenecks such as precise co-evaporation of high-end materials and reproducibility of processes.

PVD Evaporation Sources function as the material delivery core in vacuum-based thin film deposition, serving to transform solid source materials into a directed vapor flux through controlled input of thermal energy. They operate by heating the target material

beyond its sublimation or evaporation point within a high vacuum environment, thereby generating a vapor cloud with a near-Knudsen flow characteristic. The source's design—encompassing crucible geometry, heating mechanism (resistive, electron-beam, or inductive), and thermal management—directly governs the vaporization rate, angular distribution, and material utilization efficiency. Precise control over heating power and temperature is critical to achieving stable, repeatable deposition rates and maintaining consistent film stoichiometry, particularly for alloys or compounds. The vapor flux directionality, influenced by source aperture and position relative to the substrate, dictates film thickness uniformity and step coverage capabilities across complex topographies. Furthermore, the choice of source material and its thermal interaction with the crucible or hearth is fundamental to minimizing contamination, preventing unwanted chemical reactions, and ensuring the purity of the deposited film. By providing a controllable, localized high-temperature zone for material phase transition, the evaporation source establishes the foundational conditions for depositing films with specific microstructural, compositional, and functional properties, directly impacting adhesion, density, and electrical or optical performance.

This report studies the global PVD Evaporation Source production, demand, key manufacturers, and key regions.

This report is a detailed and comprehensive analysis of the world market for PVD Evaporation Source and provides market size (US\$ million) and Year-over-Year (YoY) Growth, considering 2025 as the base year. This report explores demand trends and competition, as well as details the characteristics of PVD Evaporation Source that contribute to its increasing demand across many markets.

Highlights and key features of the study

Global PVD Evaporation Source total production and demand, 2021-2032, (K Units)

Global PVD Evaporation Source total production value, 2021-2032, (USD Million)

Global PVD Evaporation Source production by region & country, production, value, CAGR, 2021-2032, (USD Million) & (K Units), (based on production site)

Global PVD Evaporation Source consumption by region & country, CAGR, 2021-2032 & (K Units)

U.S. VS China: PVD Evaporation Source domestic production, consumption, key

domestic manufacturers and share

Global PVD Evaporation Source production by manufacturer, production, price, value and market share 2021-2026, (USD Million) & (K Units)

Global PVD Evaporation Source production by Type, production, value, CAGR, 2021-2032, (USD Million) & (K Units)

Global PVD Evaporation Source production by Application, production, value, CAGR, 2021-2032, (USD Million) & (K Units)

This report profiles key players in the global PVD Evaporation Source market based on the following parameters - company overview, production, value, price, gross margin, product portfolio, geographical presence, and key developments. Key companies covered as a part of this study include 3M, Plansee, Kennametal(Sintec Group), Neyco, RD Mathis, Kurt J. Lesker, Supervac Industries, Demaco Vacuum, Shandong Pengcheng Advanced Ceramics, Qingzhou Dongshan, etc.

This report also provides key insights about market drivers, restraints, opportunities, new product launches or approvals.

Stakeholders would have ease in decision-making through various strategy matrices used in analyzing the World PVD Evaporation Source market

Detailed Segmentation:

Each section contains quantitative market data including market by value (US\$ Millions), volume (production, consumption) & (K Units) and average price (US\$/Unit) by manufacturer, by Type, and by Application. Data is given for the years 2021-2032 by year with 2025 as the base year, 2026 as the estimate year, and 2027-2032 as the forecast year.

Global PVD Evaporation Source Market, By Region:

United States

China

Europe

Japan

South Korea

ASEAN

India

Rest of World

Global PVD Evaporation Source Market, Segmentation by Type:

Tungsten Evaporation Source

Molybdenum Evaporation Source

Tantalum Evaporation Source

Other Materials

Global PVD Evaporation Source Market, Segmentation by Form:

Flat Boat Sources

Notched Boat Sources

Covered Boat Sources

Global PVD Evaporation Source Market, Segmentation by Application:

Metallizing Process

Thin Film Deposition

Others

Companies Profiled:

3M

Plansee

Kennametal(Sintec Group)

Neyco

RD Mathis

Kurt J. Lesker

Supervac Industries

Demaco Vacuum

Shandong Pengcheng Advanced Ceramics

Qingzhou Dongshan

Zibo Sinri Advanced Ceramic

Shandong Jonye Ceramics

Beijing ATTL

Luoyang Achemetal

Guangzhou Materionix

Key Questions Answered:

1. How big is the global PVD Evaporation Source market?
2. What is the demand of the global PVD Evaporation Source market?
3. What is the year over year growth of the global PVD Evaporation Source market?

4. What is the production and production value of the global PVD Evaporation Source market?
5. Who are the key producers in the global PVD Evaporation Source market?
6. What are the growth factors driving the market demand?

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